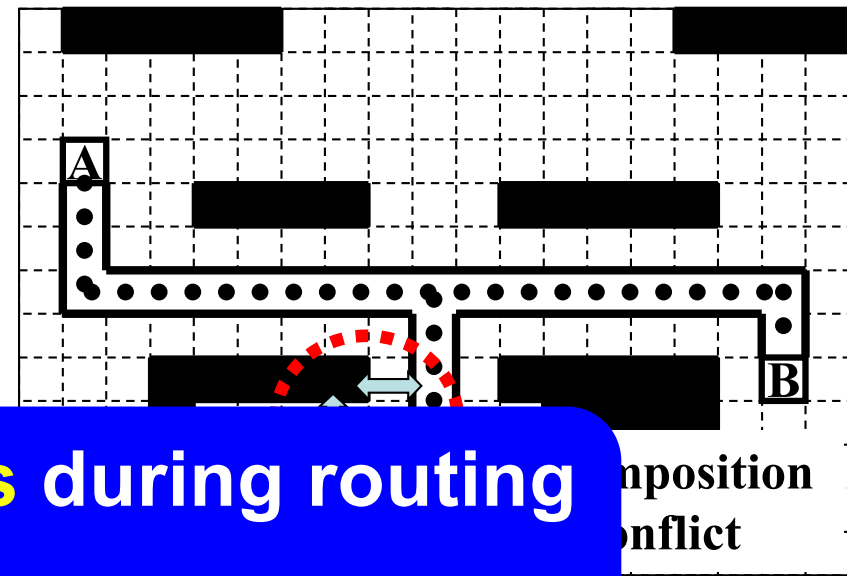
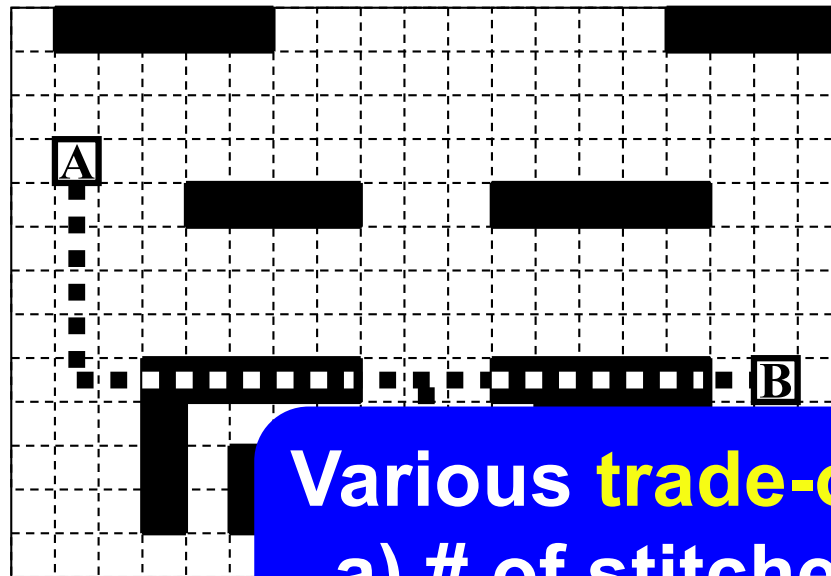


# **Double/Triple Patterning Aware Detailed Routing**

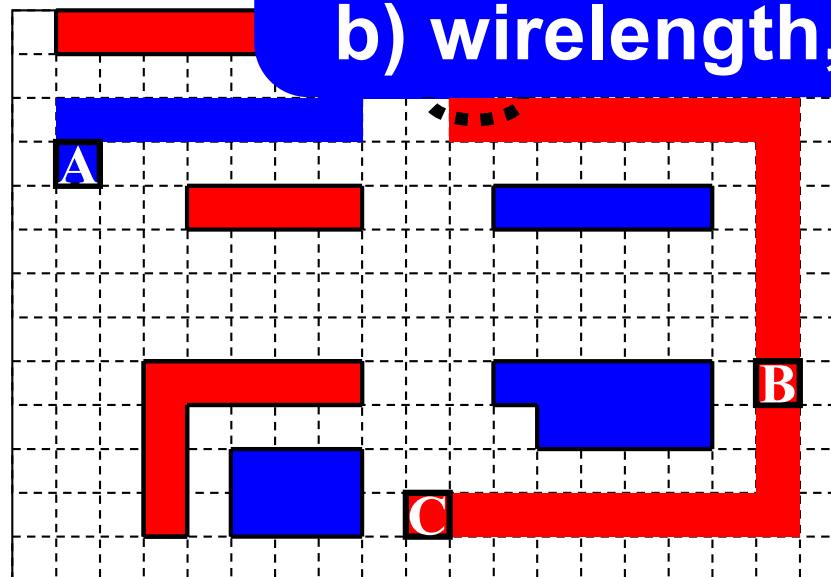
# Motivational Example



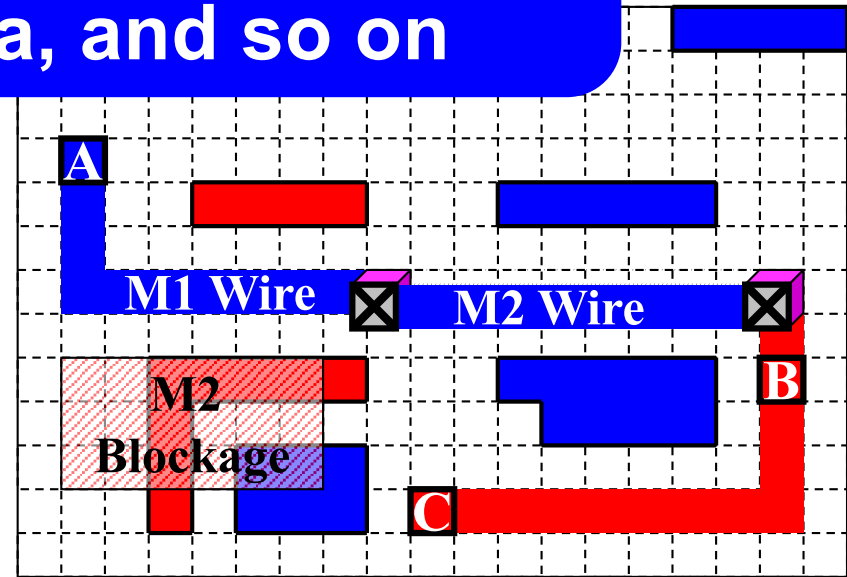
Various **trade-offs** during routing

a) # of stitches

b) wirelength, via, and so on



WL=34, Stitch=1



WL=28, Via=2

# DPL-Aware Routing

## ◆ Given

- › Netlist
- › Routing grid
- › Minimum spacing requirement
- › Two masks (colors)

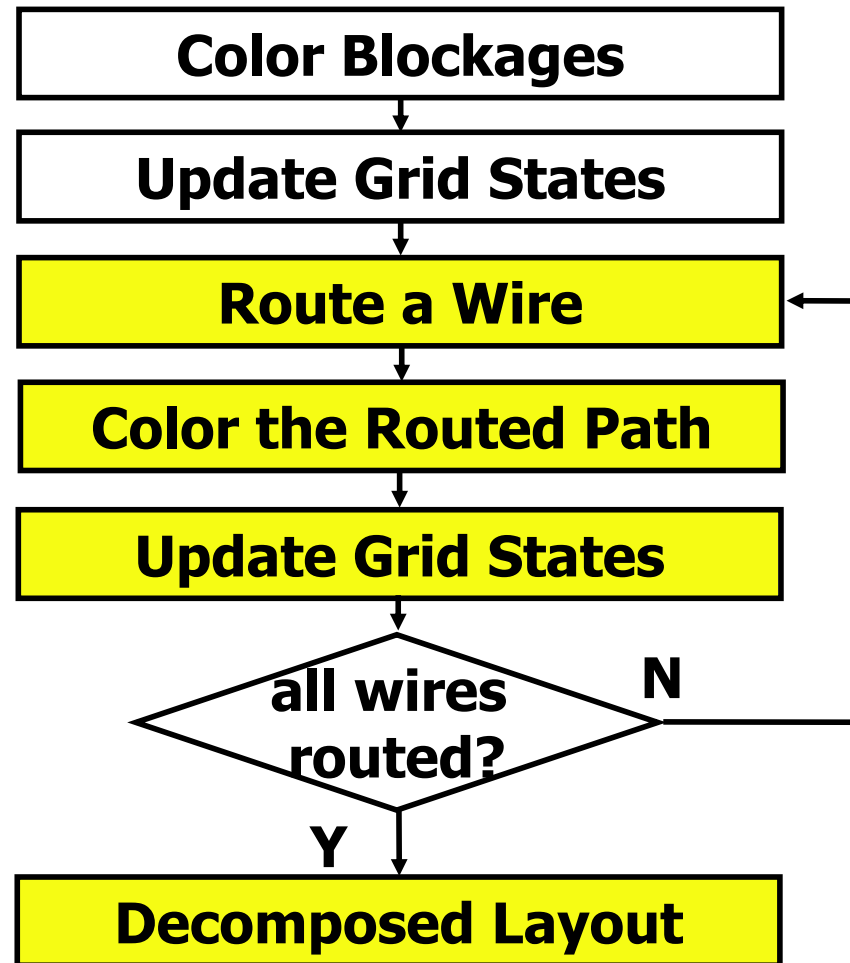
## ◆ Objective

- › Route the nets with simultaneous color assignment
- › Minimize the total wirelength, the number of stitches, vias and coloring conflicts

# **Double Patterning Technology Friendly Detailed Routing**

Minsik Cho, Yongchan Ban, David Z. Pan

# Overall Flow

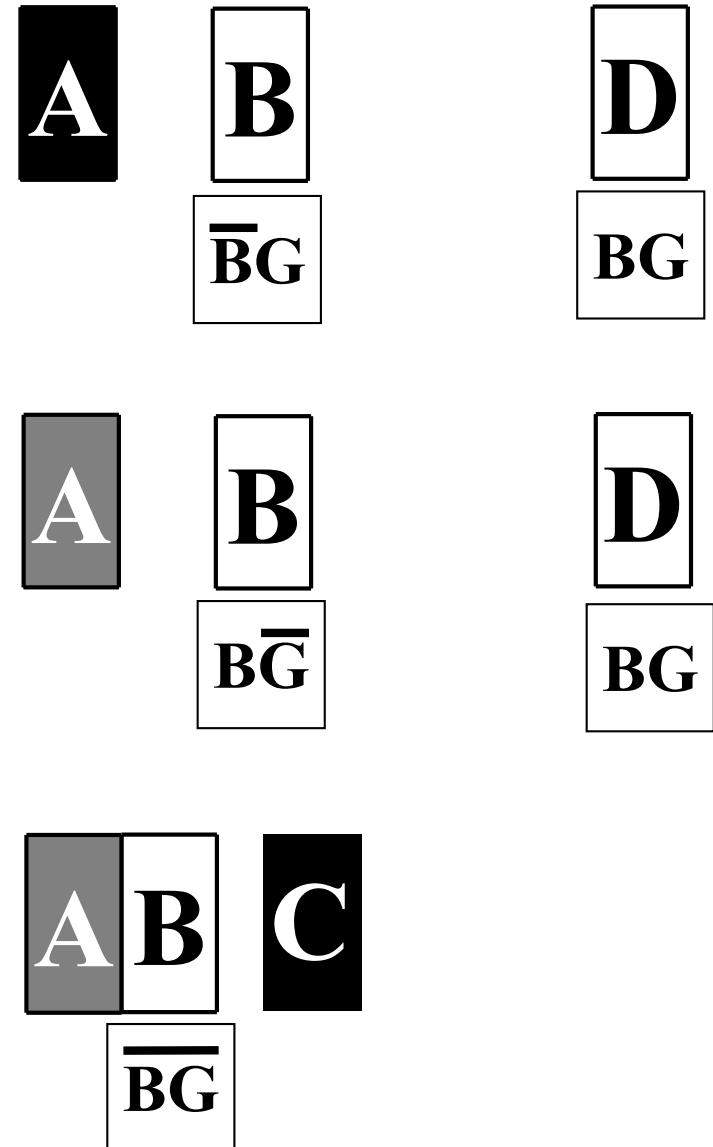


- ◆ **Simultaneous routing and decomposition**
- ◆ No additional step for layout decomposition

# Grid State for DPT

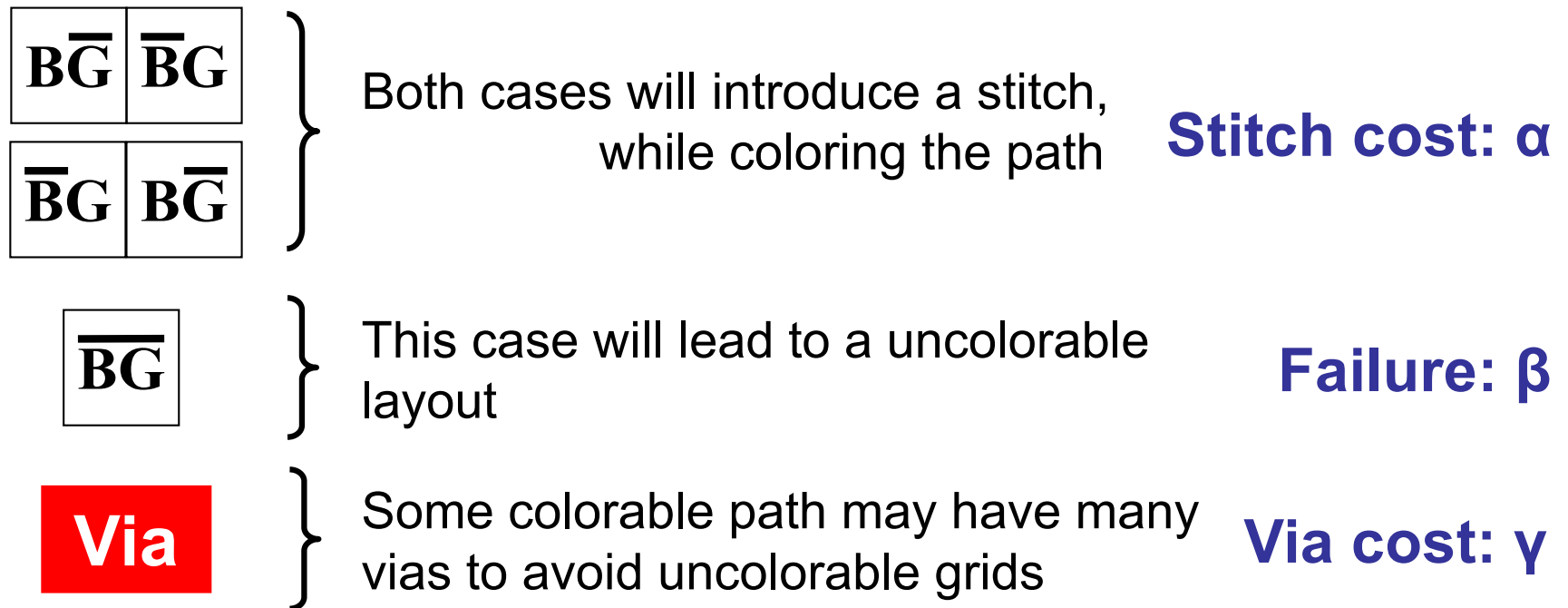
- ♦ Four possible states for each routing grid using a 2-bit variable – small overhead

$B\bar{G}$	Black-colorable Existence of grey-colored objects in the proximity
$\bar{B}G$	Grey-colorable Existence of black-colored objects in the proximity
$\bar{B}\bar{G}$	Uncolorable Existence of grey and black-colored objects in the proximity
$BG$	Bicolorable Non-existence of any colored objects in the proximity



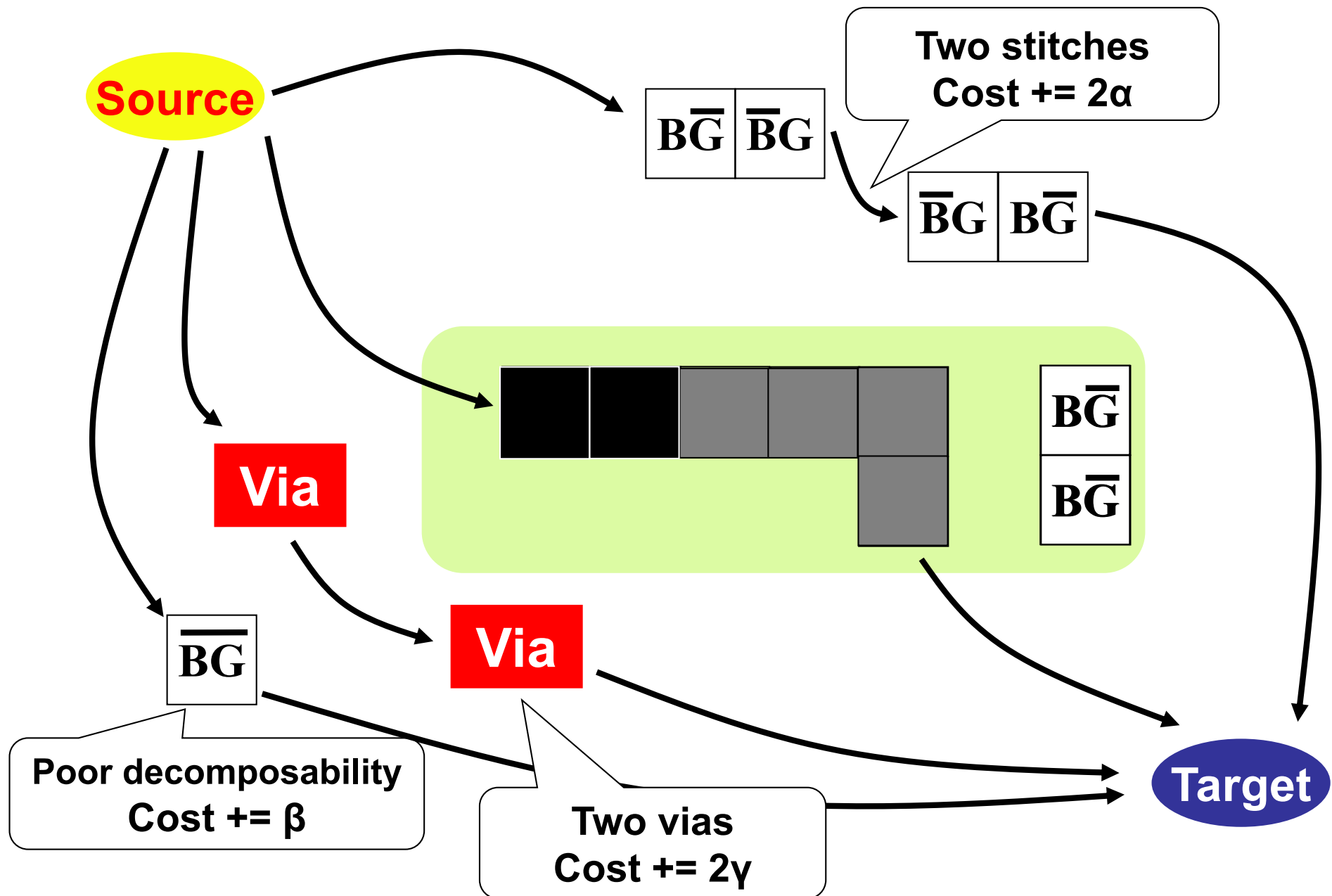
# Penalty for DPT-Unfriendly Path

- While finding a path during routing, the following cases along the path are penalized



- Perform a detailed routing using the A\* search
- Additional cost modification to find a path

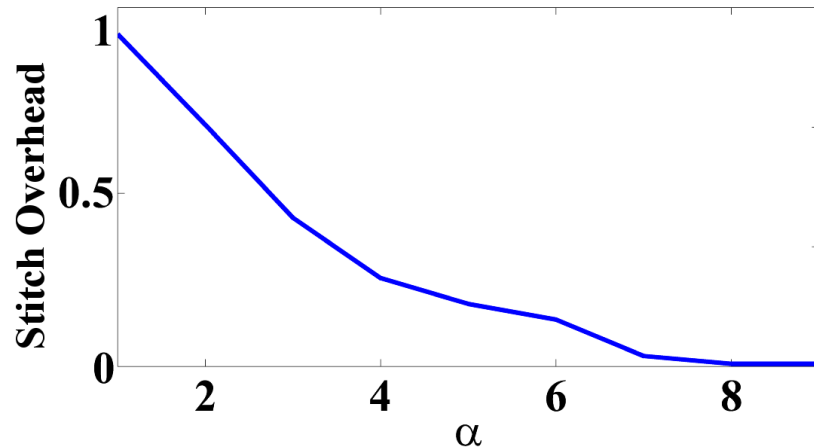
# Penalty for DPT-Unfriendly Path



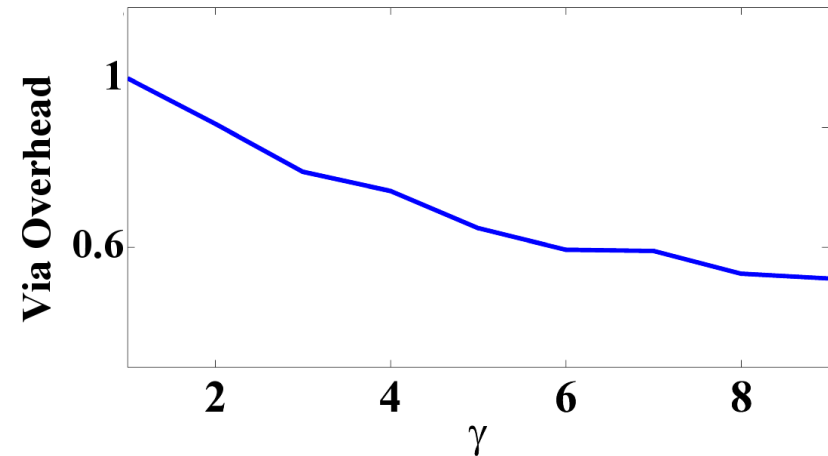


# Penalty overhead of the DPFR

- ◆ Stitch reduction by  $\alpha$  cost



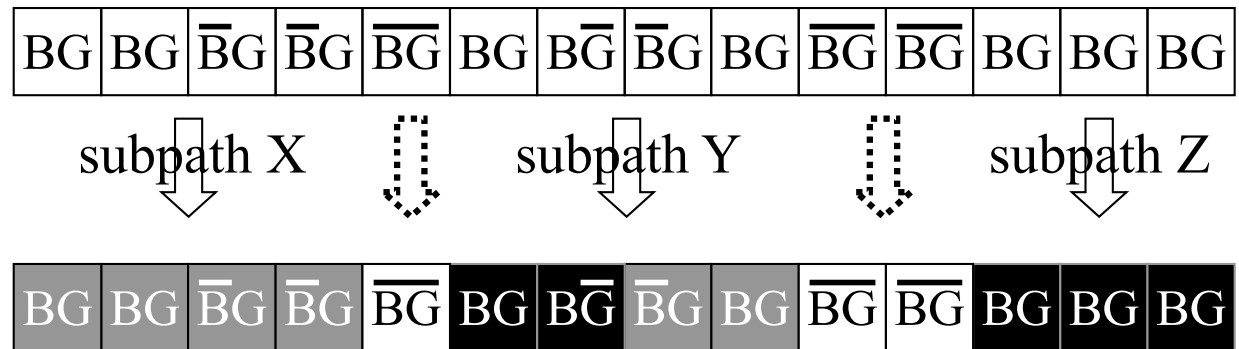
- ◆ Via reduction by  $\gamma$  cost



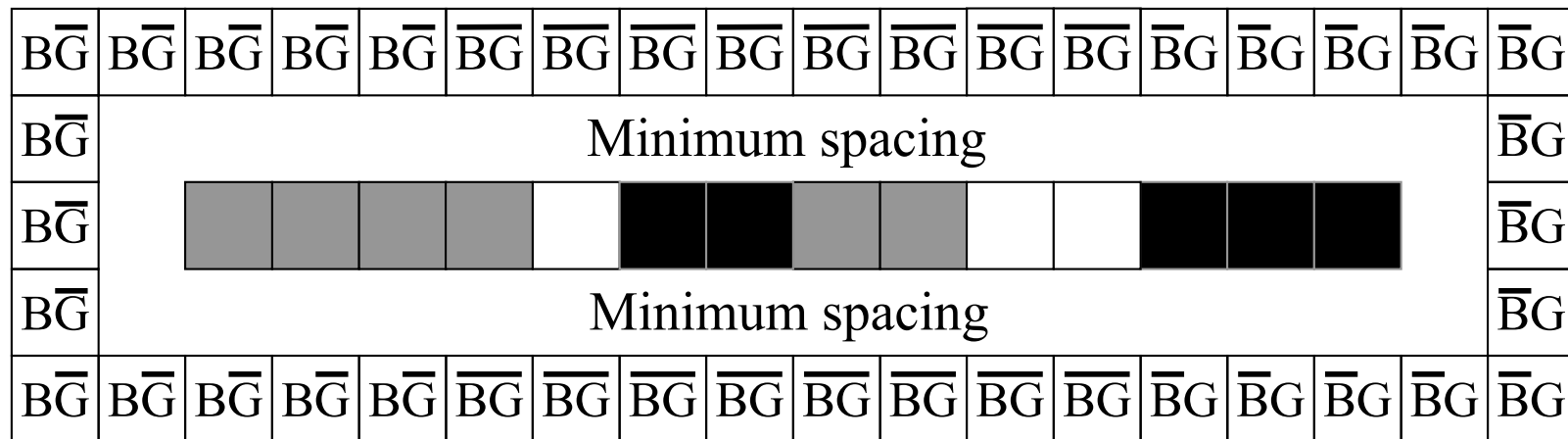
- ◆ More  $\alpha$  penalty to the routing cost to discourage stitches.
- ◆ More  $\gamma$  penalty to decrease the # of vias.
- ◆  $\beta \gg \alpha$  to minimize the number of uncolored grids.
- ◆ **Adjust the penalty costs with the degree of manufacturing difficulty.**

# Coloring Path & Shadow

## ♦ Routing Path Coloring



## ♦ Color Shadow

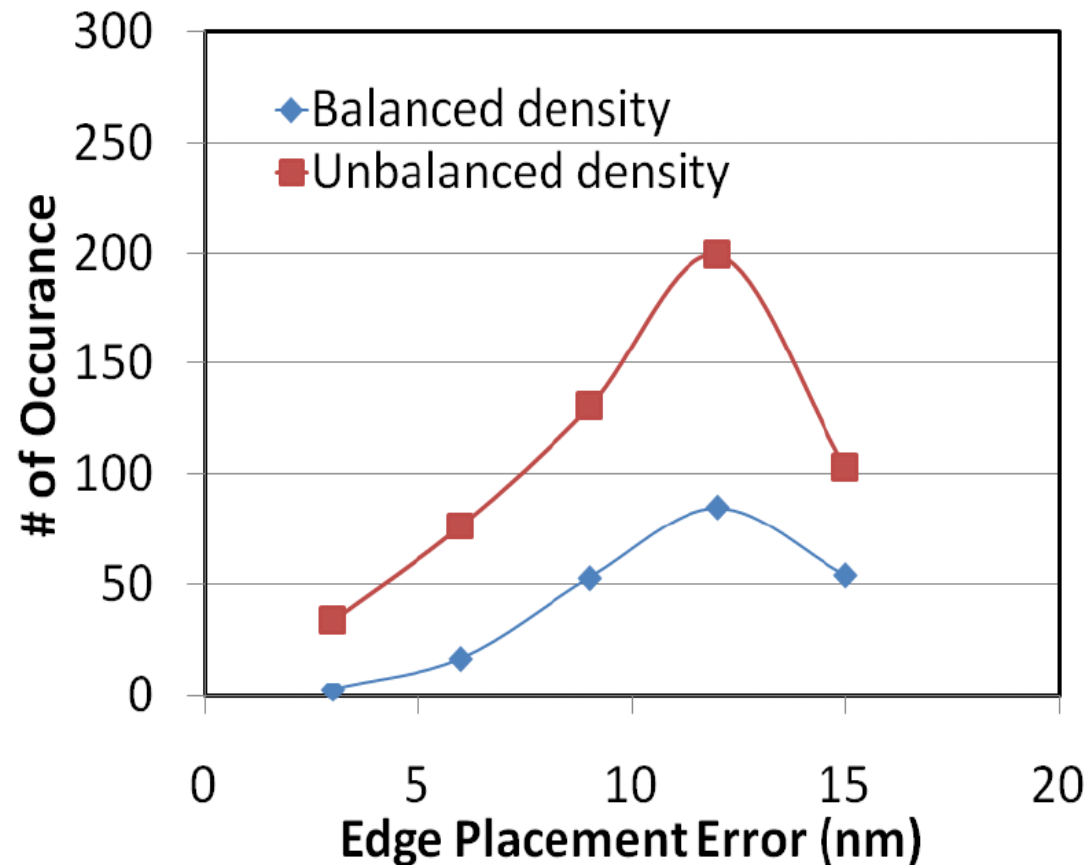


# **Double Patterning-Aware Detailed Routing with Mask Usage Balancing**

**Seong-I Lei, Chris Chu and Wai-Kei Mak**

# Introduction

- Balanced mask usage can enhance layout printability



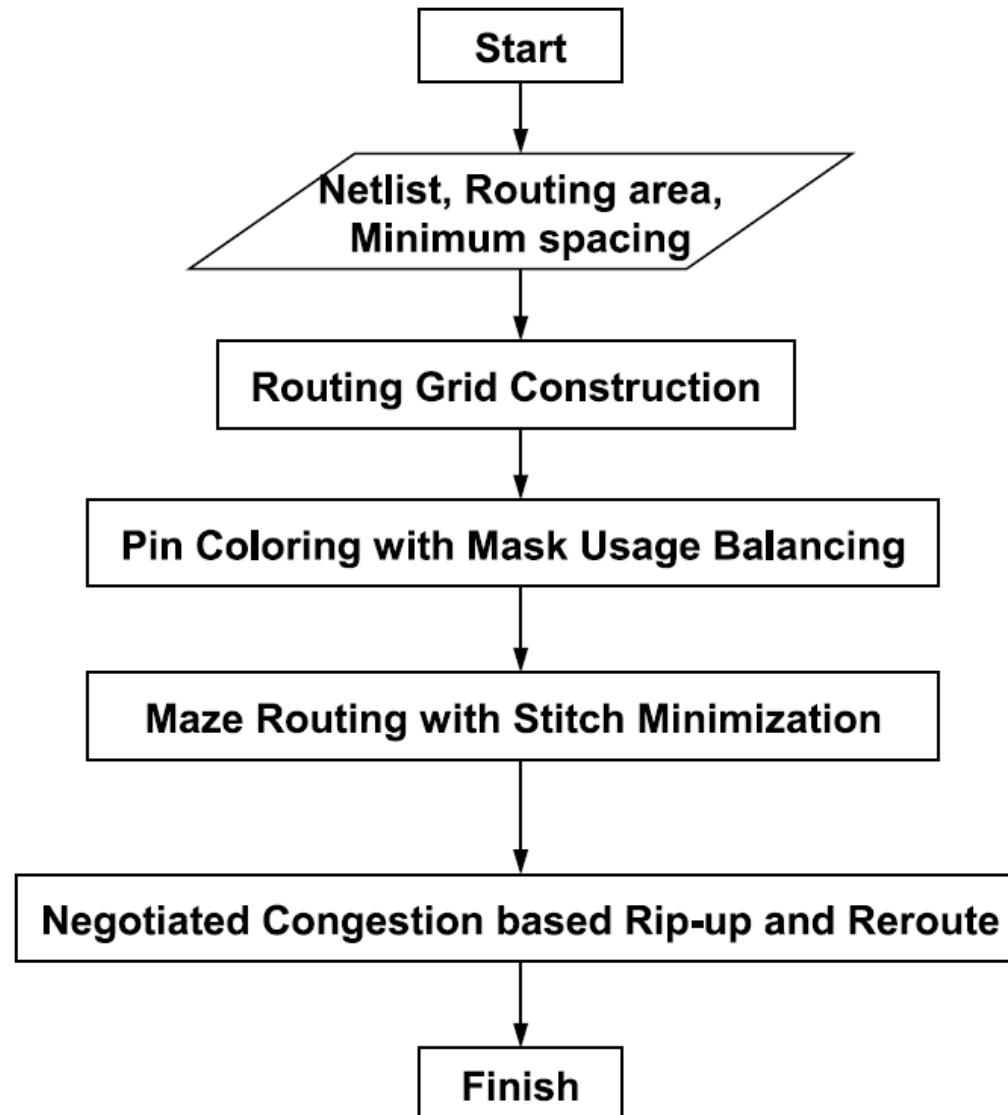
**Unbalanced:**

**RED 27% BLUE  
73%**

**Balanced:**

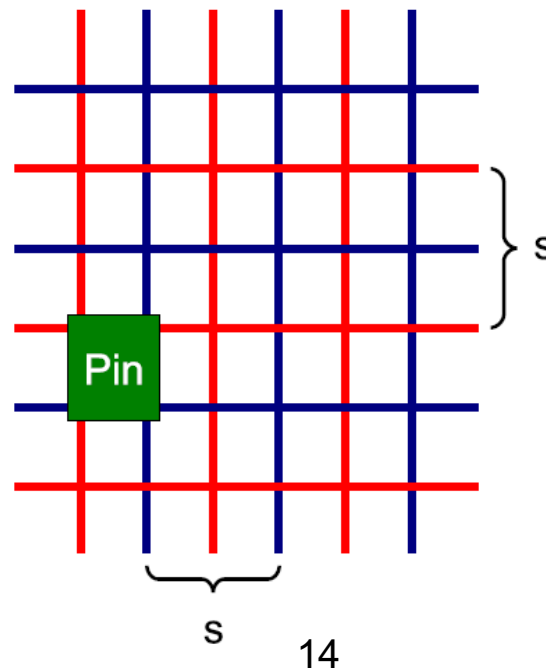
**RED 50% BLUE  
50%**

# Overall Flow



# Routing Grid Construction

- A uniform grid and the color of each track is defined before routing
- Each track is assigned either RED or BLUE and adjacent tracks in horizontal or vertical direction must be assigned different colors



# ILP-Based Pin Coloring with Mask Usage Balancing

- Determine the coloring assignment of a pin for later routing stage.
- Balance the mask usage of the two colors.
- Parameters and variables used in the ILP formulation.

Parameters	
$N$	the total number of nets
$\alpha$	the lower bound of the coloring ratio
Variables	
$p_a$	0-1 integer variable that $p_a = 1$ if pin $a$ is assigned to a RED track and $p_a = 0$ otherwise
$s_j$	0-1 integer variable that $s_j = 1$ means net $j$ will have at least one stitch and $s_j = 0$ otherwise

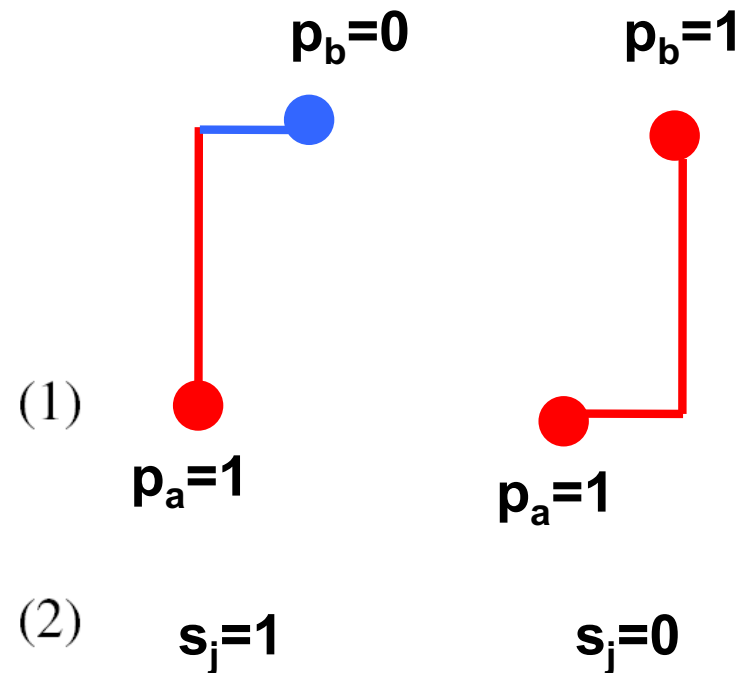
# ILP-Based Pin Coloring with Mask Usage Balancing

- The number of stitches is minimized in the objective.

$$\min \sum_{j=1}^N s_j$$

$$s.t. \quad p_a - p_b \leq s_j \quad \forall \text{net } j(a,b)$$

$$p_a - p_b \geq -s_j \quad \forall \text{net } j(a,b)$$

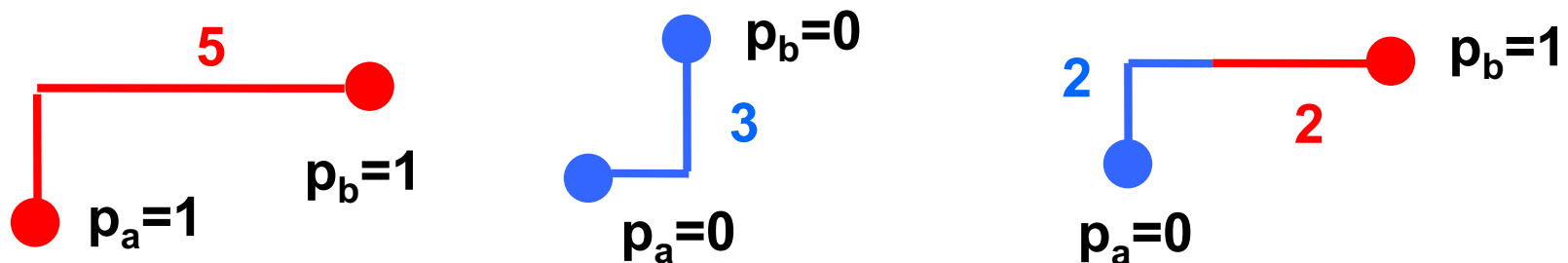




# ILP-Based Pin Coloring with Mask Usage Balancing

- Constraint (3) for mask usage balancing.

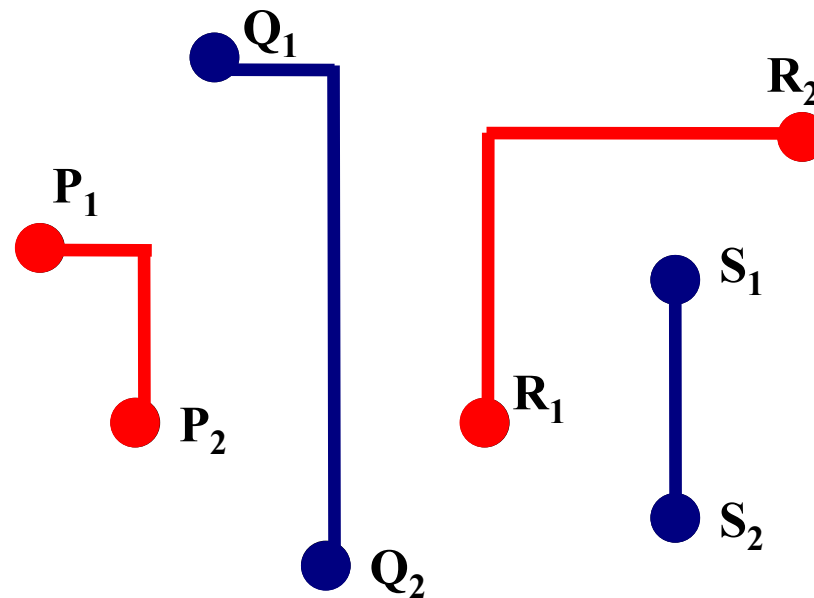
$$\alpha \leq \sum_{j=1}^N \frac{0.5HPWL_j}{totalHPWL} (p_a + p_b) \leq 1 - \alpha \quad (3)$$



**RED coloring ratio =  $(5+0+2)/(5+3+4) = 0.58$**

# ILP-Based Pin Coloring with Mask Usage Balancing

- Pin coloring stage can help to reduce the number of stitches and balance the mask usage.



# Maze Routing with Stitch Minimization

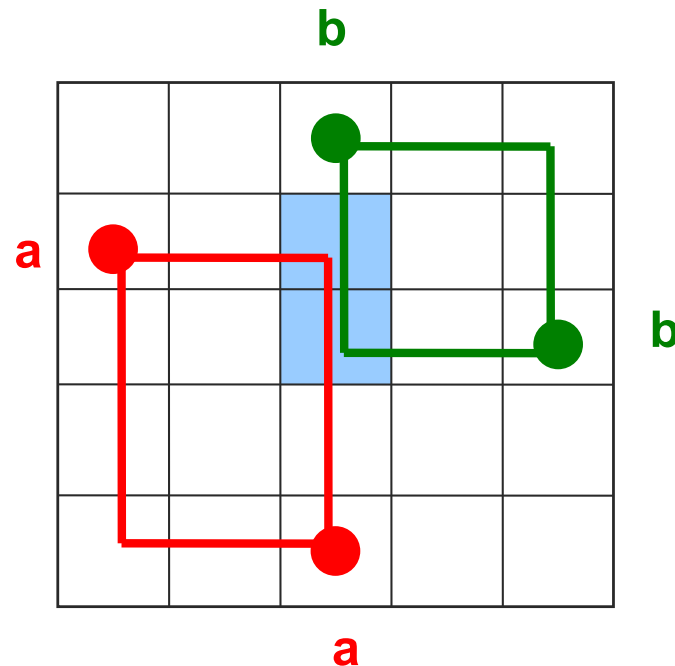
- We use A\* search algorithm to perform maze routing.
- Minimize WL, the number of stitches and vias.
- If the solution propagates to a different color track, a stitch cost is added to the cost function.
- If the solution propagates to another layer, a via cost is added to the cost function.

# Maze Routing with Stitch Minimization

- After solving the ILP, if the two pins of a net are assigned to the same color, we will perform the maze routing using only the tracks of that color.
- Otherwise, we perform the maze routing using all the tracks.

# Negotiated Congestion based Rip-up and Reroute

- We adopt a negotiated congestion based routing scheme in rip-up and reroute.

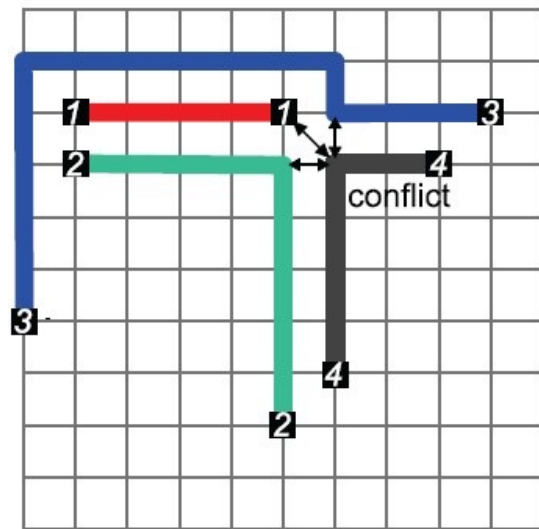


# **TPL Aware Routing and Its Comparison with Double Patterning Aware Routing in 14nm Technology**

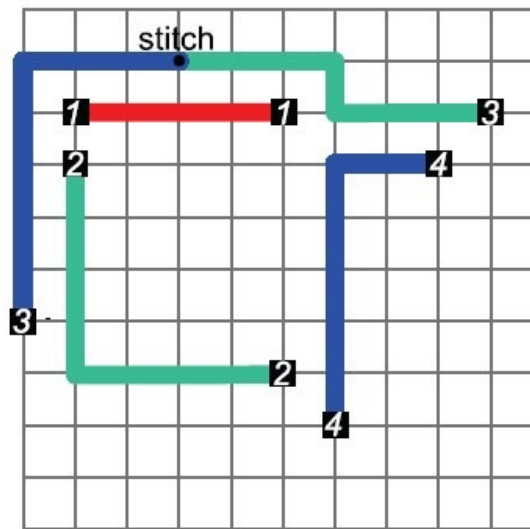
**Q. Ma, H. Zhang, M.D.F. Wong**

# TPL Aware Routing

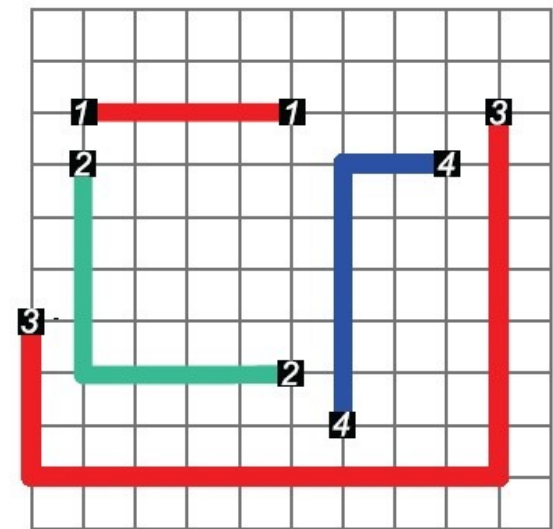
- ◆ Most hard-to-decompose features are generated during the routing stage
- ◆ Considering TPL during routing can improve the layout decomposability



(a)



(b)



(c)

# TPL Aware Routing

## ◆ Given

- › Netlist
- › Routing grid
- › Minimum spacing requirement
- › Three masks (colors)

## ◆ Objective

- › Route the nets with simultaneous color assignment
- › Minimize total color-conflicting wire length
- › Minimize number of stitches

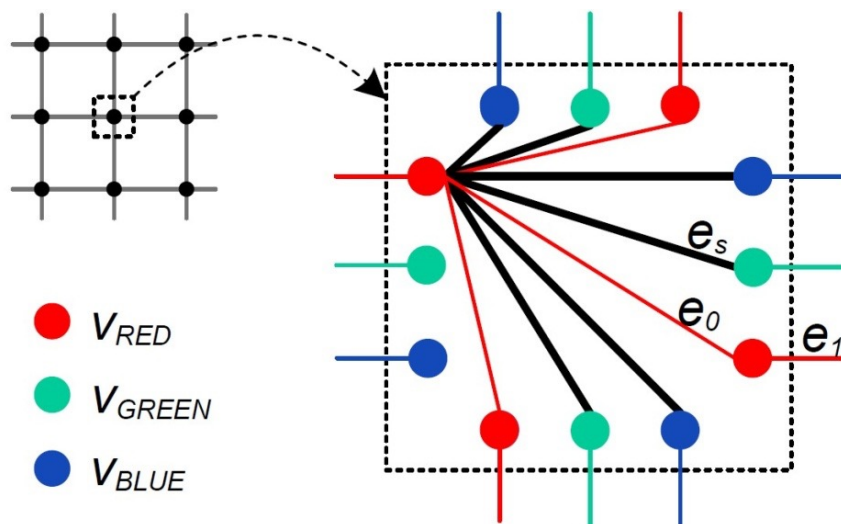


# TPL Aware Maze Routing

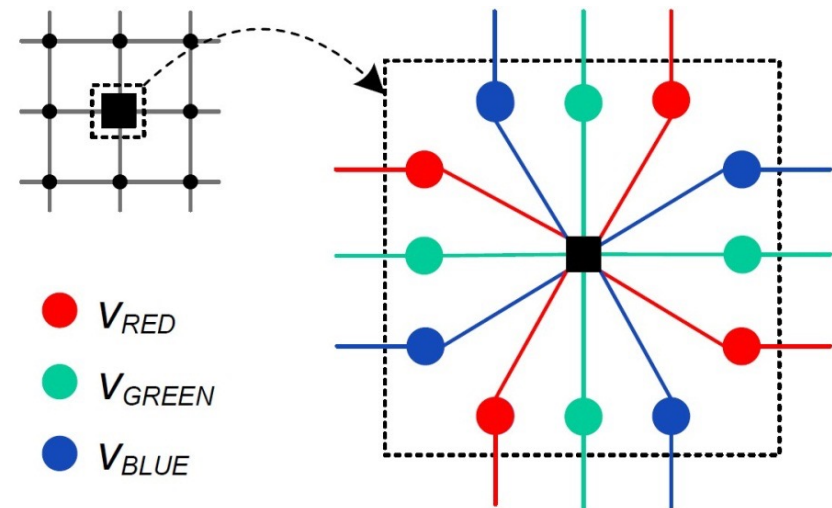
## ◆ Route a single net

- › In presence of previously routed nets with color assignment
- › Minimize weighted sum of wire-length, color-conflicting wire-length and number of stitches

## ◆ Graph splitting approach



**Graph model for a non-terminal vertex**

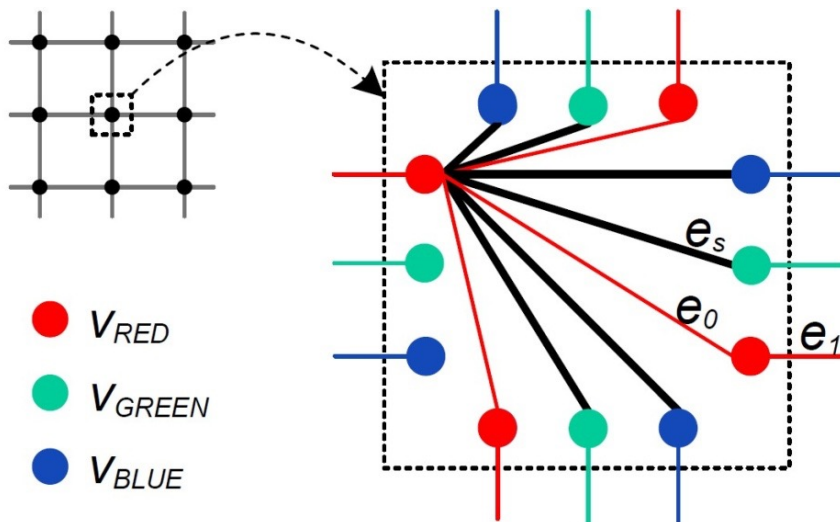


**Graph model for a terminal vertex**

# TPL Aware Maze Routing (Cont')

## ◆ Graph splitting approach

- › Each intersection is modeled by a set of 12 nodes with associated edges
- › At each intersection, type  $e_s$  edge implies the use of a stitch while type  $e_0$  edge implies no stitch used there
- › Type  $e_1$  edge between two same colored nodes from adjacent intersections



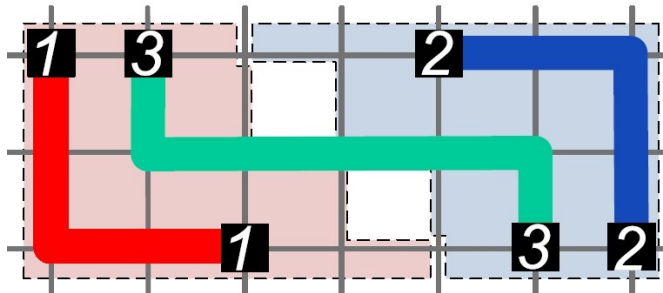
cost of type  $e_0$  edge = 0

cost of type  $e_s$  edge = penalty of a stitch

cost of type  $e_1$  edge  
= 1 if no conflict with any previously  
routed and colored nets;  
or 1 + penalty of a unit of color-  
conflicting wire length, otherwise

# TPL Aware Maze Routing (Cont')

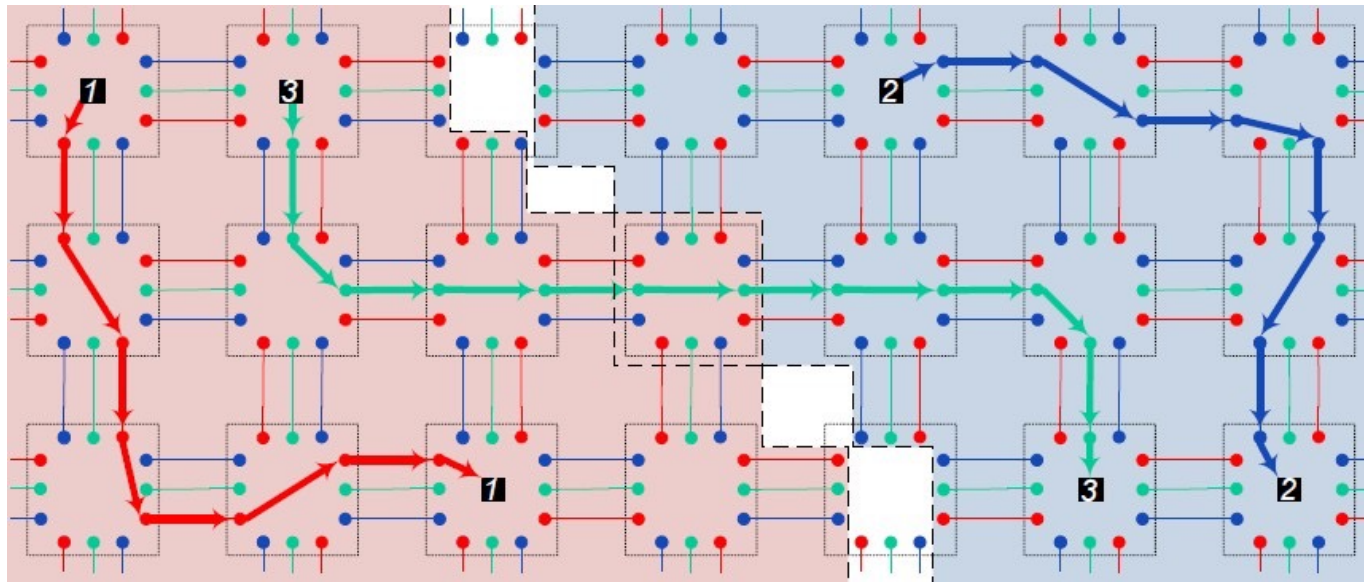
## ♦ Example



**Routes on  
the original  
grid**

Assume net routing  
order is: 1, 2, 3

blue conflict region after  
routing & coloring net 2

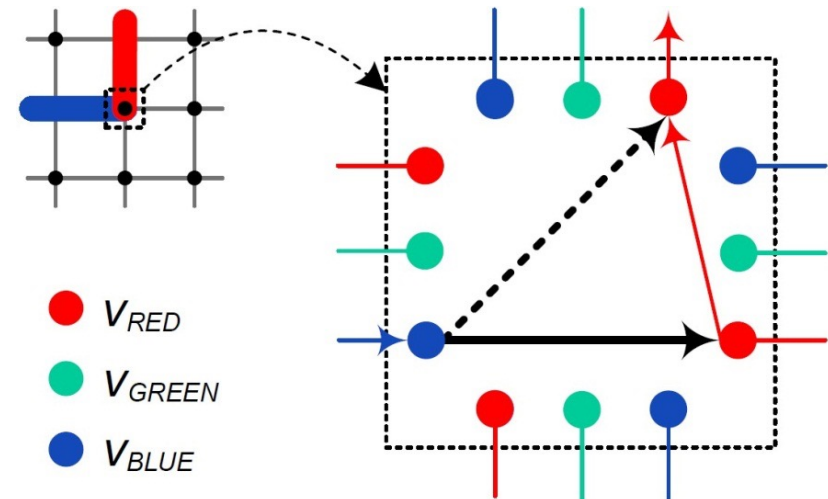
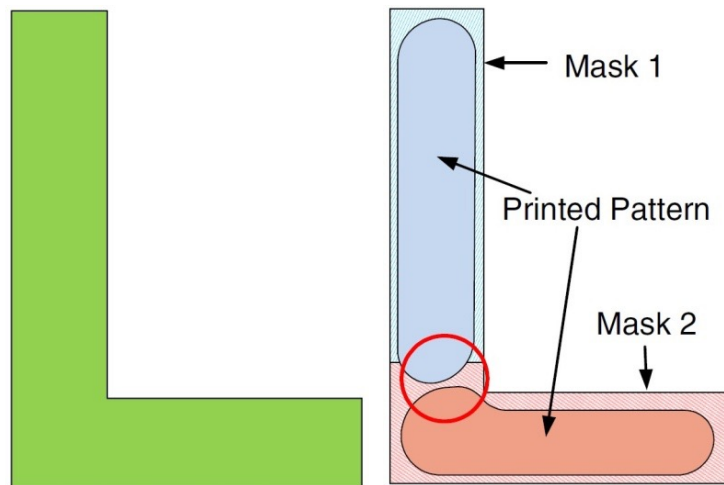


**Routes on  
the  
expanded  
graph**

red conflict region after  
routing & coloring net 1

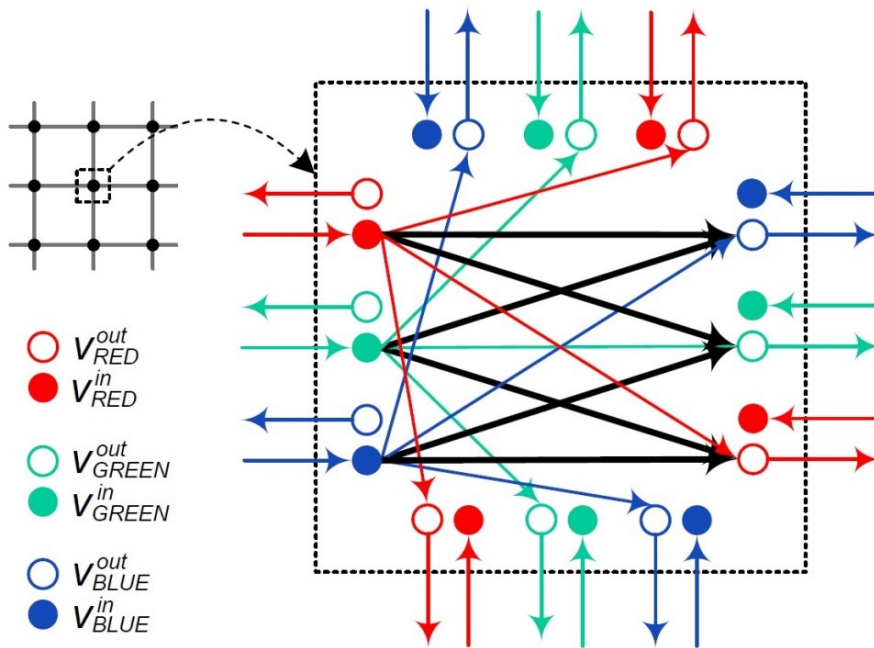
# Forbidding Stitch at Corner

- ◆ Corner stitch is undesirable
  - › Overlay error
  - › Line-end effect
- ◆ Adapt our graph model to forbid stitch at corner
  - › Remove the edges corresponding to corner stitches
  - › Not done yet!

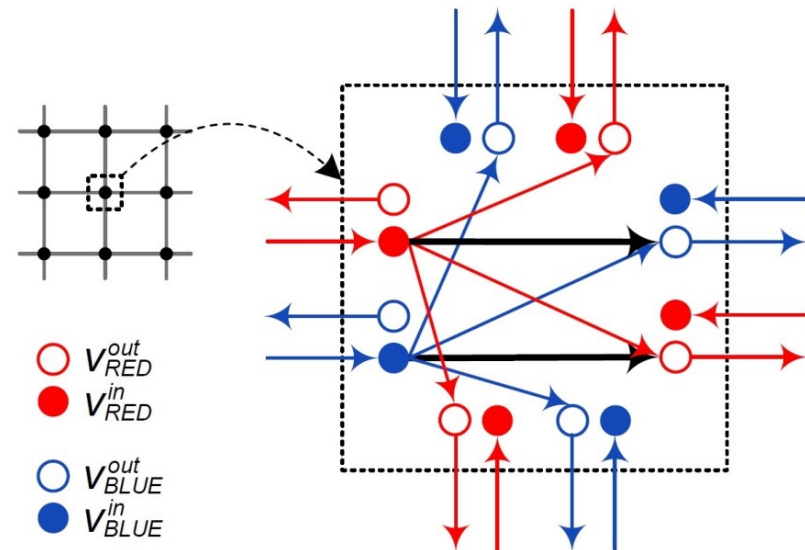


# Forbidding Stitch at Corner (Cont')

- ◆ Further split the graph
  - › Each vertex  $v$  is split into  $v^{in}$  and  $v^{out}$
  - › Each edge within the original graph model is directed from a  $v^{in}$  to a  $v^{out}$



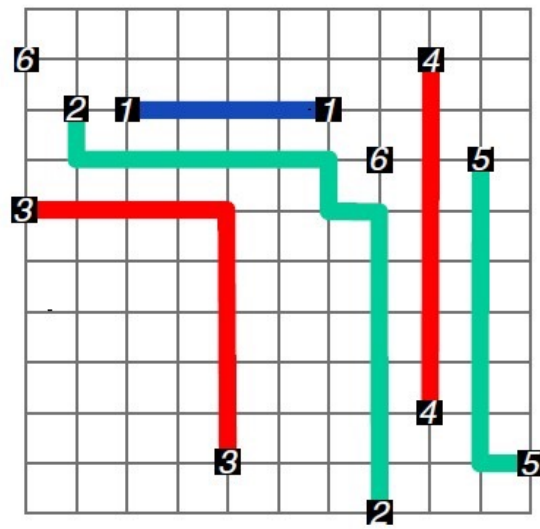
**Graph model for  
TPL**



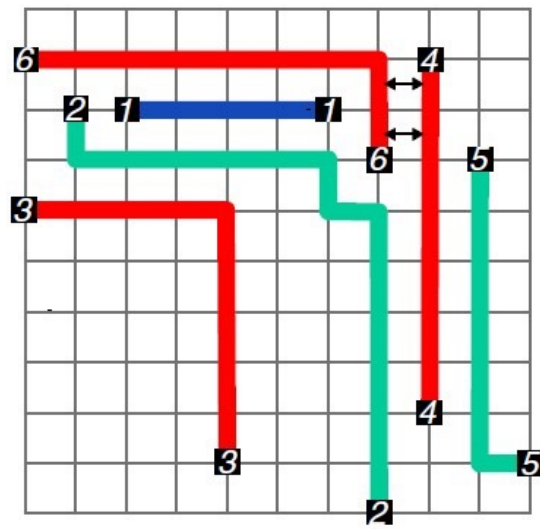
**Graph model for  
DPL**

# Overall Routing Scheme

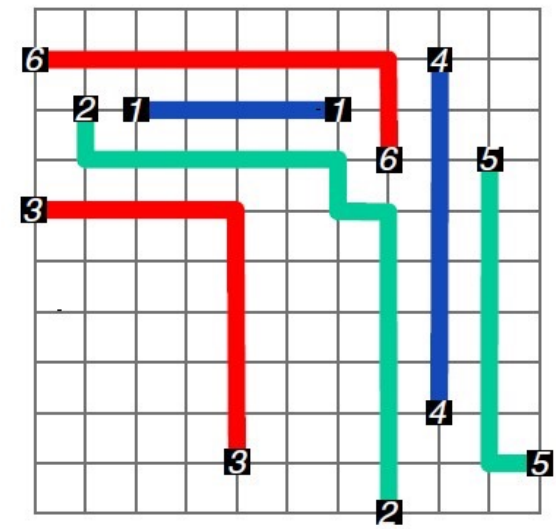
- ◆ Route all nets one by one without resource sharing
- ◆ Edges where color-conflicts occurred become more costly
- ◆ Nets with color-conflicts are iteratively rerouted



(a)



(b)



(c)

# Overall Routing Scheme (Cont')

- ◆ Balancing features on three masks
  - › Ensures that each mask is fully utilized
  - › Helps the printability enhancement
- ◆ We effectively control the balancing on the fly
  - › Keep track of the total wire length in each color  $l_{Red}$ ,  $l_{Green}$ ,  $l_{Blue}$
  - › Set edge cost proportional to total wire length in each color
    - »  $c_{Red}/l_{Red} = c_{Green}/l_{Green} = c_{Blue}/l_{Blue}$
    - » The more edges in this color are used, the more expensive the edges in this color will be



# References

- ◆ [Cho+ ICCAD08] Double Patterning Technology Friendly Detailed Routing
- ◆ [Lei+ ISQED2014] Double Patterning-Aware Detailed Routing with Mask Usage Balancing
- ◆ [Ma+ DAC2012] TPL Aware Routing and Its Comparison with Double Patterning Aware Routing in 14nm Technology